# This Page is Inserted by IFW Indexing and Scanning Operations and is not part of the Official Record

# BEST AVAILABLE IMAGES

Defective images within this document are accurate representations of the original documents submitted by the applicant.

Defects in the images include but are not limited to the items checked:

BLACK BORDERS

IMAGE CUT OFF AT TOP, BOTTOM OR SIDES

FADED TEXT OR DRAWING

BLURRED OR ILLEGIBLE TEXT OR DRAWING

SKEWED/SLANTED IMAGES

COLOR OR BLACK AND WHITE PHOTOGRAPHS

GRAY SCALE DOCUMENTS

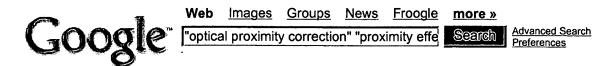
LINES OR MARKS ON ORIGINAL DOCUMENT

IMAGES ARE BEST AVAILABIÆ COPY.

OTHER:

As rescanning these documents will not correct the image problems checked, please do not report these problems to the IFW Image Problem Mailbox.

☐ REFERENCE(S) OR EXHIBIT(S) SUBMITTED ARE POOR QUALITY



Web Results 1 - 10 of about 354 for "optical proximity correction" "proximity effects". (0.23 seconds)

Synopsys Products - Optical Proximity Correction

... an advanced set of tools that embed **Optical Proximity Correction** (OPC) into ... Causes include reticle pattern fidelity, optical **proximity effects**, and diffusion ... www.synopsys.com/products/ntimrg/opc\_ds.html - 9k - <u>Cached</u> - <u>Similar pages</u>

Optical Proximity Correction using Proteus, Progen & Prospector ... Optical Proximity Correction using Proteus, Progen & Prospector. ... Prerequisites Basic knowledge of lithography, optical proximity effects and Unix navigational ... www.synopsys.com/cgi-bin/ces/detail.cgi?id=1314 - 11k - Cached - Similar pages [More results from www.synopsys.com]

#### **DuPont Photomasks, Inc.**

... capability to support the broad range of **optical proximity correction** (OPC) techniques ... with subwavelength features causes what is known as '**proximity effects**'. ... www.photomask.com/technology/binary.html - 28k - <u>Cached</u> - <u>Similar pages</u>

#### **IntroMEMS**

... Technologies' **Optical Proximity Correction** (OPC) Services Introduction to OPC Techniques used to correct and analyze optical **proximity effects** are becoming ... www.benchmarktech.com/Svcs\_OPCservices.htm - 12k - Cached - Similar pages

#### **ProdSoftware**

... offers advanced approaches and techniques to implement **optical proximity correction** by adding ... services correct your device data for optical **proximity effects**. ... www.benchmarktech.com/Prod Software.htm - 8k - Cached - Similar pages

#### Future Fab Intl.

... this requires sophisticated application of **Optical Proximity Correction** (OPC) techniques to ... onto the wafer surface, so-called "proximity effects"can distort ... www.future-fab.com/documents.asp?grID=213&d\_ID=2311 - 52k - <u>Cached</u> - <u>Similar pages</u>

System and method for performing optical proximity correction on ...

... ensure that no **proximity effects** will occur between elements fully integrated in different cells. A one-dimensional **optical proximity correction** technique is ... www.patentalert.com/docs/000/z00039321.shtml - 7k - <u>Cached - Similar pages</u>

#### Introduction to the Product

... OPTISSIMO is able to restrict **optical proximity correction** to critical areas on ... proximity effect; simulation of optical **proximity effects** multiple illumination ... www.aiss.de/OPTISSIMO/OPTISSIMO.html - 10k - <u>Cached</u> - <u>Similar pages</u>

#### Optical Microlithography X

... Optical **proximity effects** correction at 0.25 µm incorporating process variations in ... **Optical proximity correction** of alternating phase-shift masks for 0.18-µm ... www.spie.org/web/meetings/programs/ml97/ml97\_3051.html - 23k - <u>Cached</u> - <u>Similar pages</u>

#### MaskTools' News

... Optical proximity effects occur when a chip has features that are smaller than the ...

A dominant technology used in RET is optical proximity correction (OPC). ... www.masktools.com/content/cadence\_2k4.htm - 22k - Cached - Similar pages

Goooooooogle ▶

Result Page:

1 2 3 4 5 6 7 8 9 10

**Next** 

"optical proximity correction" "pro Search



Search within results | Language Tools | Search Tips | Dissatisfied? Help us improve

Google Home - Advertising Programs - Business Solutions - About Google ©2004 Google





Subscribe (Full Service) Register (Limited Service, Free) Login

Search: 

The ACM Digital Library

+"optical proximity correction" +offset\*

SEARCH



Feedback Report a problem Satisfaction survey

#### Terms used optical proximity correction offset

Found 5 of 144.254

Sort results by Display

results



Save results to a Binder Search Tips Open results in a new

Try an Advanced Search Try this search in The ACM Guide

Results 1 - 5 of 5

Relevance scale

1 A methodology for modeling the effects of systematic within-die interconnect and device variation on circuit performance

Vikas Mehrotra, Shiou Lin Sam, Duane Boning, Anantha Chandrakasan, Rakesh Vallishayee, Sani Nassif

June 2000 Proceedings of the 37th conference on Design automation

window

Full text available: pdf(1.01 MB) Additional Information: full citation, abstract, references, citings, index terms

We present a methodology to study the impact of spatial pattern dependent variation on circuit performance and implement the technique in a CAD framework. We investigate the effects of interconnect CMP and poly CD device variation on interconnect delay and clock skew in both aluminum and copper interconnect technology. Our results indicate that interconnect CMP variation strongly affects interconnect delay, while poly CD variation has a large impact on clock skew in a 1 GHz design. Given th ...

<sup>2</sup> A pattern matching algorithm for verification and analysis of very large IC layouts Mariusz Niewczas, Wojciech Maly, Andrzej Strojwas April 1998 Proceedings of the 1998 international symposium on Physical design

Full text available: pdf(922.02 KB)

Additional Information: full citation, abstract, references, citings, index terms

We propose a simple, isometry invariant pattern matching algorithm for an effective data reduction useful in layout-related data processing of very complex IC designs. The repeatable geometrical features and attributes are stored in a pattern database. Original pattern instance, or its geometrical attributes, may be quickly regenerated based both on the information stored within the pattern and position of the pattern instance. We also show preliminary results of analysis of the state-of-th ...

3 Session 7: Lithography and Routing: What's Next? (invited): Layout impact of resolution [ enhancement techniques: impediment or opportunity?

Lars W. Liebmann

April 2003 Proceedings of the 2003 international symposium on Physical design

Full text available: pdf(374.96 KB) Additional Information: full citation, abstract, references, citings, index terms

This tutorial introduces the reader to the basic concepts of optical lithography, derives fundamental resolution limits, reviews the challenges facing future technology nodes, explains the principles of resolution enhancement techniques and their impact on chip layout, and discusses layout optimization considerations.

**Keywords**: design for manufacturability, lithography, radically restricted designs, resolution



enhancement techniques

4 Design for manufacturability in submicron domain
W. Maly, H. Heineken, J. Khare, P. K. Nag
January 1997 Proceedings of the 1996 IEEE/ACM international conference on Computer- aided design
Full text available: pdf(236.63 KB)  Additional Information: full citation, abstract, references, citings, index terms
Publisher Site
Key characteristics of newly emerging IC technologies render the traditional concept of die size minimization and traditional "design rules" insufficient to handle the design-manufacturing interface. This tutorial surveys the design and process characteristics relevant to the manufacturability of submicron ICs. The discussion also covers analysis of design for manufacturability (DFM) trade-offs. Yield and cost models needed to analyze these trade-offs
are explained as well.
<b>Keywords</b> : IC technologies, cost model, design for manufacturability, design rules, die size minimization, integrated circuit technology, submicron domain, trade-offs, yield
5 ASIC design in nanometer era - dead or alive?: Exploring regular fabrics to optimize the
<u>performance-cost trade-off</u> L. Pileggi, H. Schmit, A. J. Strojwas, P. Gopalakrishnan, V. Kheterpal, A. Koorapaty, C. Patel, V. Rovner, K. Y. Tong
June 2003 Proceedings of the 40th conference on Design automation
Full text available: pdf(319.99 KB) Additional Information: full citation, abstract, references, citings, index terms
While advances in semiconductor technologies have pushed achievable scale and performance to phenomenal limits for ICs, nanoscale physical realities dictate IC production based on what we can afford. We believe that IC design and manufacturing can be made more affordable, and reliable, by removing some design and implementation flexibility and enforcing new forms of design regularity. This paper discusses some of the trade-offs to consider for determination of how much regularity a particular IC
Keywords: cost, integrated circuits, performance, regularity
Results 1 - 5 of 5
The ACM Portal is published by the Association for Computing Machinery. Copyright © 2004 ACM, Inc.
Terms of Usage Privacy Policy Code of Ethics Contact Us
Useful downloads: Adobe Acrobat Q QuickTime Windows Media Player Real Player



Subscribe (Full Service) Register (Limited Service, Free) Login

+"optical proximity correction" +"proximity effect correction"

SEARCH



Feedback Report a problem Satisfaction survey

#### Terms used optical proximity correction proximity effect correction

Found 1 of 144.254

Sort results

by Display results



Save results to a Binder

Open results in a new window

Try an Advanced Search Try this search in The ACM Guide

Results 1 - 1 of 1

<sup>1</sup> Embedded tutorial: subwavelength lithography

Tsuneo Terasawa

January 2000 Proceedings of the 2000 conference on Asia South Pacific design automation

Full text available: pdf(84.78 KB)

Additional Information: full citation, references

Results 1 - 1 of 1

The ACM Portal is published by the Association for Computing Machinery. Copyright @ 2004 ACM, Inc. Terms of Usage Privacy Policy Code of Ethics Contact Us

Useful downloads: Adobe Acrobat QuickTime Windows Media Player

Real Player

Relevance scale ...

IEEE HOME | SEARCH IEEE | SHOP | WEB ACCOUNT | CONTACT IEEE



Membership Publications/Services Standards Conferences Careers/Jobs



IEEE/	Welcome United States Patent and Trademark Office	2
Help FAQ Terms IEE	EE Peer Review Quidic Links ☑	» Se
Welcome to IEEE Xplore®  - Home - What Can I Access? - Log-out	Your search matched 1 of 1085387 documents. A maximum of 500 results are displayed, 15 to a page, sorted by Relevance Descending order.	ance
Tables of Contents	<b>Refine This Search:</b> You may refine your search by editing the current search expression or end one in the text box.	nteri
O- Journals & Magazines	'optical proximity correction' <and> 'proximity effect ( Search</and>	
O- Conference Proceedings	■ Check to search within this result set	*
O- Standards	Results Key:  JNL = Journal or Magazine CNF = Conference STD = Standard	
Search		
O- By Author O- Basic O- Advanced O- CrossRef	<ul> <li>Low energy e-beam proximity lithography (LEEPL)         Utsumi, T.;</li> <li>Microprocesses and Nanotechnology Conference, 1999. Digest of Papers.         Microprocesses and Nanotechnology '99. 1999 International , 6-8 July 1999 Pages: 32 - 33</li> </ul>	99
Member Services		
O- Join IEEE O- Establish IEEE Web Account	[Abstract] [PDF Full-Text (92 KB)] IEEE CNF	
O Access the IEEE Member Digital Library		
IEEE Enterprise		
O- Access the IEEE Enterprise File Cabinet		

Print Format

Home | Log-out | Journals | Conference Proceedings | Standards | Search by Author | Basic Search | Advanced Search | Join IEEE | Web Account |
New this week | OPAC Linking Information | Your Feedback | Technical Support | Email Alerting | No Robots Please | Release Notes | IEEE Online
Publications | Help | FAQ | Terms | Back to Top

Copyright © 2004 IEEE - All rights reserved



eb Images Groups News Froogle

more » Search

Advanced Search Preferences

Web

Results 1 - 7 of about 565 for "yoshizawa keiji ". (0.41 seconds)

Did you mean: "yoshizawa kenji"

# リリース・リスト(英語版), discog-english

... is Delated). PSF-5 (LP) PSFD-5 (CD), Kan Mikami, Moto **Yoshizawa**, **Keiji** Haino, Live in 1st Year of Heisei vol.1 (LP is Delated). PSF-6 ... homepage2.nifty.com/PSF/index\_e.html - 48k - <u>Cached</u> - <u>Similar pages</u>

#### mail-order

... US\$26.1) m-/m- Geino Yamashirogumi "Songs of Silk-Road" LP Invitation VIH28028 price:3000yen (US\$26.1) m-/m- ★Kan Mikami/Motoharu **Yoshizawa/Keiji** Haino "上 ... homepage2.nifty.com/paganmusik/omega/foreign.html - 34k - <u>Cached</u> - <u>Similar pages</u> [ <u>More results from homepage2.nifty.com</u> ]

# 【五四三音樂站】 - [ Translate this page ]

... PSF - 1 High Rise 1st(Ltd.300copies, Deleted)→已絕版PSFD- 2 High Rise 2nd PSFD- 3/4 Fushitsusha Live PSFD- 5 Kan Mikami, Moto **Yoshizawa**, **Keiji** Haino Live ... bbs.music543.com/ournet.pl/music543/ Prog-Kraut/archives/A0UK8MQT/A0UK8MQU - 17k - Cached - Similar pages

#### PSF Discography

... PSF-5...Kan Mikami/Moto Yoshizawa/Keiji Haino: Live in 1st Year of Heisei Vol. ... PSF-6...Kan Mikami/Moto Yoshizawa/Keiji Haino: Live in 1st Year of Heisei Vol. ... gravediggervideo.com/psf.html - 31k - <u>Cached</u> - <u>Similar pages</u>

## Abstract: Temporal integration characteristics of chromatic ...

... Temporal integration characteristics of chromatic response as determined by use of the isoluminant double-pulse method. Tatsuya **Yoshizawa**, **Keiji** Uchikawa. ... www.opticsinfobase.org/abstract.cfm?id=1881 - Similar pages

## Journal of the Optical Society of America A - Archives

... KB)] Temporal integration characteristics of chromatic response as determined by use of the isoluminant double-pulse method Tatsuya **Yoshizawa**, **Keiji** Uchikawa pp ... josaa.osa.org/browse.cfm?journal=1& volume=,14&issue=,14-9 - Similar pages

#### english

... Takinogawa hall) 1997Apr NEW WAVE COLLABORATION 2 - 'The earth, The water, The fire, The wind' Music by 1 day each, Motoharu **Yoshizawa**, **Keiji** Haino, Keisuke ... members.jcom.home.ne.jp/odt/english.html - 19k - <u>Cached</u> - <u>Similar pages</u>

In order to show you the most relevant results, we have omitted some entries very similar to the 7 already displayed.

If you like, you can repeat the search with the omitted results included.

Did you mean to search for: "yoshizawa kenji"

Free! Get the Google Toolbar. <u>Download Now</u> - <u>About Toolbar</u>

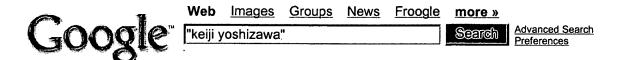
Google +	Search Web 🔻 🌠   PageRank	3 blocked 📳 AutoFill 🚾 Options
Control of the Contro	فتالا متبعث والمستعملين والمراج والمتمارة والمستعمل والمستعم والمستعمل والمستعمل والمستعمل والمستعمل والمس	استريان والمتعارف المتحارف والمتحار والمتحار والمتحارض والمتحار والمتحارف وا

"yoshizawa keiji " Search

Search within results | Language Tools | Search Tips | Dissatisfied? Help us improve

Google Home - Advertising Programs - Business Solutions - About Google

©2004 Google



Web

Results 1 - 1 of about 2 for "keiji yoshizawa". (0.43 seconds)

Did you mean: "kenji yoshizawa"

Kathodik - Shamansongs: fifteen dreams of Haino Keiji - [Translate this page] ... Jiyu No Ishi (Free Will)" di Yuji Itsumi, pubblicato recentemente dall'etichetta, che contiene ritratti di Otomo, Bailey, Keiji, Yoshizawa più altri e un CD ... www.kathodik.it/ modules.php?name=News&file=article&sid=414 - 46k - Cached - Similar pages

In order to show you the most relevant results, we have omitted some entries very similar to the 1 already displayed.

If you like, you can repeat the search with the omitted results included.

Did you mean to search for: "kenji yoshizawa"

Free! Get the Google Toolbar. Download Now - About Toolbar



"keiji yoshizawa" Search

Search within results | Language Tools | Search Tips | Dissatisfied? Help us improve

Google Home - Advertising Programs - Business Solutions - About Google

©2004 Google

IEEE HOME | SEARCH IEEE | SHOP | WEB ACCOUNT | CONTACT IEEE



# Publications/Services Standards Conferences Careers/Jobs EEE Xplore®

Welcome



	RELEASE 1.8
Help FAQ Terms IE	EE Peer Review Quick Links Se.
Welcome to IEEE Xplore®	
O- Home O- What Can I Access?	Your search matched <b>1</b> of <b>1085387</b> documents.  A maximum of <b>500</b> results are displayed, <b>15</b> to a page, sorted by <b>Relevance Descending</b> order.
O- Log-out	Refine This Search:
Tables of Contents	You may refine your search by editing the current search expression or entering new one in the text box.
O- Journals & Magazines	optical <and> proximity <and> correction <and> offs</and></and></and>
Conference Proceedings	■ Check to search within this result set
O- Standards	Results Key:  JNL = Journal or Magazine CNF = Conference STD = Standard
Search	July Standard Flagazine City - Conference City - Standard
O- By Author D- Basic Advanced CrossRef	1 Sub-1 /spl mu/m/sup 2/ high density embedded SRAM technologie 100 nm generation SOC and beyond Tomita, K.; Hashimoto, K.; Inbe, T.; Oashi, T.; Tsukamoto, K.; Nishioka, Y.; Matsuura, M.; Eimori, T.; Inuishi, M.; Miyanaga, I.; Nakamura, M.; Kishimoto, Yamada, T.; Eriguchi, K.; Yuasa, H.; Satake, T.; Kajiya, A.; Ogura, M.;
Member Services  O- Join IEEE	VLSI Technology, 2002. Digest of Technical Papers. 2002 Symposium on , 11- June 2002 Pages: 14 - 15
O- Establish IEEE Web Account	[Abstract] [PDF Full-Text (373 KB)] IEEE CNF
O- Access the IEEE Member Digital Library	
IEEE Enterprise	
O- Access the IEEE Enterprise File Cabinet	

Print Format

Home | Log-out | Journals | Conference Proceedings | Standards | Search by Author | Basic Search | Advanced Search | Join IEEE | Web Account |
New this week | OPAC Linking Information | Your Feedback | Technical Support | Email Alerting | No Robots Please | Release Notes | IEEE Online
Publications | Help | FAQ | Terms | Back to Top

Copyright © 2004 IEEE - All rights reserved



Subscribe (Full Service) Register (Limited Service, Free) Login

Search: 

The ACM Digital Library 

The Guide

+optical +proximity +correct\* +offset\*

SEARCH



Feedback Report a problem Satisfaction survey

Terms used optical proximity correct offset

Found 41 of 144,254

Sort results by Display

results



Save results to a Binder

Search Tips

Open results in a new

Try an <u>Advanced Search</u>
Try this search in <u>The ACM Guide</u>

.

Results 1 - 20 of 41

Result page: **1** <u>2</u> <u>3</u>

Relevance scale 🔲 🔲 📰 🔳

1 A methodology for modeling the effects of systematic within-die interconnect and device variation on circuit performance

Vikas Mehrotra, Shiou Lin Sam, Duane Boning, Anantha Chandrakasan, Rakesh Vallishayee, Sani Nassif

June 2000 Proceedings of the 37th conference on Design automation

window

Full text available: pdf(1.01 MB)

Additional Information: <u>full citation</u>, <u>abstract</u>, <u>references</u>, <u>citings</u>, <u>index</u> <u>terms</u>

next

We present a methodology to study the impact of spatial pattern dependent variation on circuit performance and implement the technique in a CAD framework. We investigate the effects of interconnect CMP and poly CD device variation on interconnect delay and clock skew in both aluminum and copper interconnect technology. Our results indicate that interconnect CMP variation strongly affects interconnect delay, while poly CD variation has a large impact on clock skew in a 1 GHz design. Given th ...

Session 7: Lithography and Routing: What's Next? (invited): Layout impact of resolution enhancement techniques: impediment or opportunity? Lars W. Liebmann

April 2003 Proceedings of the 2003 international symposium on Physical design

Full text available: pdf(374.96 KB)

Additional Information: <u>full citation</u>, <u>abstract</u>, <u>references</u>, <u>citings</u>, <u>index</u> <u>terms</u>

This tutorial introduces the reader to the basic concepts of optical lithography, derives fundamental resolution limits, reviews the challenges facing future technology nodes, explains the principles of resolution enhancement techniques and their impact on chip layout, and discusses layout optimization considerations.

 $\textbf{Keywords} \colon \text{design for manufacturability, lithography, radically restricted designs, resolution enhancement techniques}$ 

3 Automatic spelling correction in scientific and scholarly text Joseph J. Pollock, Antonio Zamora

April 1984 Communications of the ACM, Volume 27 Issue 4

Full text available: pdf(901.06 KB) Additional Information: full citation, references, citings, index terms

**Keywords**: dictionary lookup, similarity keys, spelling correction

4 A framework for realistic image synthesis



Donald P. Greenberg, Kenneth E. Torrance, Peter Shirley, James Arvo, Eric Lafortune, James A. Ferwerda, Bruce Walter, Ben Trumbore, Sumanta Pattanaik, Sing-Choong Foo August 1997 Proceedings of the 24th annual conference on Computer graphics and interactive techniques

Full text available: pdf(28.94 MB)

Additional Information: full citation, references, citings, index terms

**Keywords**: light reflection, perception, realistic image synthesis

5 The office of the future: a unified approach to image-based modeling and spatially immersive displays



Ramesh Raskar, Greg Welch, Matt Cutts, Adam Lake, Lev Stesin, Henry Fuchs July 1998 Proceedings of the 25th annual conference on Computer graphics and interactive techniques

Full text available: pdf(2.00 MB)

Additional Information: full citation, references, citings, index terms

Keywords: autocalibration, calibration, depth, display, image-based modeling, image-based rendering, intensity blending, projection, range, reflectance, spatially immersive display, virtual environments

6 Making faces



Brian Guenter, Cindy Grimm, Daniel Wood, Henrique Malvar, Fredric Pighin July 1998 Proceedings of the 25th annual conference on Computer graphics and interactive techniques

Full text available: 🔁 pdf(1.70 MB) Additional Information: full citation, references, citings, index terms

Computer puppetry: An importance-based approach Hyun Joon Shin, Jehee Lee, Sung Yong Shin, Michael Gleicher April 2001 ACM Transactions on Graphics (TOG), Volume 20 Issue 2



Full text available: pdf(1.04 MB)

Additional Information: full citation, abstract, references, citings, index terms

Computer puppetry maps the movements of a performer to an animated character in realtime. In this article, we provide a comprehensive solution to the problem of transferring the observations of the motion capture sensors to an animated character whose size and proportion may be different from the performer's. Our goal is to map as many of the important aspects of the motion to the target character as possible, while meeting the online, real-time demands of computer puppetry. We adopt a K ...

**Keywords**: Human-figure animation, motion retargetting, performance-based animation, real-time animation

The power crust

Nina Amenta, Sunghee Choi, Ravi Krishna Kolluri



# May 2001 Proceedings of the sixth ACM symposium on Solid modeling and applications

Full text available: pdf(1.17 MB)

Additional Information: <u>full citation</u>, <u>abstract</u>, <u>references</u>, <u>citings</u>, <u>index</u> terms

The *power crust* is a construction which takes a sample of points from the surface of a three-dimensional object and produces a surface mesh and an approximate medial axis. The approach is to first approximate the medial axis transform (MAT) of the object. We then use an inverse transform to produce the surface representation from the MAT.

This idea leads to a simple algorithm with theoretical guarantees comparable to those of other surface reconstruction and medial axis approxi ...

A pattern matching algorithm for verification and analysis of very large IC layouts

Mariusz Niewczas, Wojciech Maly, Andrzej Strojwas

April 1998 Proceedings of the 1998 international symposium on Physical design

Full text available: pdf(922.02 KB)

Additional Information: <u>full citation</u>, <u>abstract</u>, <u>references</u>, <u>citings</u>, <u>index</u> <u>terms</u>

We propose a simple, isometry invariant pattern matching algorithm for an effective data reduction useful in layout-related data processing of very complex IC designs. The repeatable geometrical features and attributes are stored in a pattern database. Original pattern instance, or its geometrical attributes, may be quickly regenerated based both on the information stored within the pattern and position of the pattern instance. We also show preliminary results of analysis of the state-of-th ...

10 Emancipated pixels: real-world graphics in the luminous room

John Underkoffler, Brygg Ullmer, Hiroshi Ishii

July 1999 Proceedings of the 26th annual conference on Computer graphics and interactive techniques

Full text available: pdf(613.18 KB) Additional Information: full citation, references, citings, index terms

**Keywords**: CAD, architectural space, computer vision, luminous-tangible interfaces, projection, real-world graphics

11 The digital Michelangelo project: 3D scanning of large statues

Marc Levoy, Kari Pulli, Brian Curless, Szymon Rusinkiewicz, David Koller, Lucas Pereira, Matt Ginzton, Sean Anderson, James Davis, Jeremy Ginsberg, Jonathan Shade, Duane Fulk July 2000 Proceedings of the 27th annual conference on Computer graphics and interactive techniques

Full text available: pdf(10.83 MB)

Additional Information: <u>full citation</u>, <u>abstract</u>, <u>references</u>, <u>citings</u>, <u>index</u> terms

We describe a hardware and software system for digitizing the shape and color of large fragile objects under non-laboratory conditions. Our system employs laser triangulation rangefinders, laser time-of-flight rangefinders, digital still cameras, and a suite of software for acquiring, aligning, merging, and viewing scanned data. As a demonstration of this system, we digitized 10 statues by Michelangelo, including the well-known figure of David, two building interiors, and all 1,163 extant f ...

**Keywords**: 3D scanning, cultural heritage, graphics systems, mesh generation, range images, rangefinding, reflectance and shading models, sensor fusion

# 12 An experimental laboratory for pattern recognition and signal processing

N. M. Herbst, P. M. Will

April 1972 Communications of the ACM, Volume 15 Issue 4

Full text available: pdf(2.02 MB)

Additional Information: full citation, abstract, references

An interactive computer-controlled scanning and display system has been in operation at the IBM Thomas J. Watson Research Center for three years. The system includes two flying-spot scanners and a TV camera specially interfaced to a process control digital computer, dotmode and vector displays, analog input and output facilities, and a variety of other experimental equipment. The system design and programming support are described and typical applications in scanner control, optical charac ...

Keywords: image processing, interactive terminal, pattern recognition, pseudorandom displays, scanners

# 13 Query evaluation techniques for large databases

Goetz Graefe

June 1993 ACM Computing Surveys (CSUR), Volume 25 Issue 2

Full text available: pdf(9.37 MB)

Additional Information: full citation, abstract, references, citings, index terms, review

Database management systems will continue to manage large data volumes. Thus, efficient algorithms for accessing and manipulating large sets and sequences will be required to provide acceptable performance. The advent of object-oriented and extensible database systems will not solve this problem. On the contrary, modern data models exacerbate the problem: In order to manipulate large sets of complex objects as efficiently as today's database systems manipulate simple records, query-processi ...

Keywords: complex query evaluation plans, dynamic query evaluation plans, extensible database systems, iterators, object-oriented database systems, operator model of parallelization, parallel algorithms, relational database systems, set-matching algorithms, sort-hash duality

# 14 Graphic applications subroutine packages

William L. Dunne

July 1968 Proceedings of the 5th annual workshop on Design automation

Full text available: pdf(1.28 MB) Additional Information: full citation, abstract, index terms

The Graphic Applications Subroutine Package, GASP, is a set of interdependent twodimentional programs capable of producing drawings on an automatic digital plotter. GASP was justified and developed in an engineering support environment to satisfy certain requirements within the workload responsibilities of a production drafting room and within the engineering areas. In FORTRAN (G or H level) for the IBM System/360, the package utilizes plotter dependent routines through a simple standard i ...

# 15 Interactive Editing Systems: Part I

Norman Meyrowitz, Andries van Dam

September 1982 ACM Computing Surveys (CSUR), Volume 14 Issue 3

Full text available: pdf(3.08 MB) Additional Information: full citation, citings, index terms

# 16 The Cricket location-support system

Nissanka B. Priyantha, Anit Chakraborty, Hari Balakrishnan

# August 2000 Proceedings of the 6th annual international conference on Mobile computing and networking

Full text available: pdf(1.22 MB) Additional Information: full citation, abstract, references, citings

This paper presents the design, implementation, and evaluation of Cricket, a location-support system for in-building, mobile, location-dependent applications. It allows applications running on mobile and static nodes to learn their physical location by using listeners that hear and analyze information from beacons spread throughout the building. Cricket is the result of several design goals, including user privacy, decentralized administrat ...

17 PARO: supporting dynamic power controlled routing in wireless ad hoc networks
Javier Gomez, Andrew T. Campbell, Mahmoud Naghshineh, Chatschik Bisdikian
September 2003 Wireless Networks, Volume 9 Issue 5

Full text available: pdf(311.95 KB) Additional Information: full citation, abstract, references, index terms

This paper introduces PARO, a dynamic power controlled routing scheme that helps to minimize the transmission power needed to forward packets between wireless devices in ad hoc networks. Using PARO, one or more intermediate nodes called "redirectors" elects to forward packets on behalf of source-destination pairs thus reducing the aggregate transmission power consumed by wireless devices. PARO is applicable to a number of networking environments including wireless sensor networks, home networks ...

Keywords: ad hoc networks, power control, power optimization, routing protocols

# 18 Filling and slotting: analysis and algorithms

Andrew B. Kahng, Gabriel Robins, Anish Singh, Huijuan Wang, Alexander Zelikovsky April 1998 Proceedings of the 1998 international symposium on Physical design

Full text available: pdf(1.19 MB)

Additional Information: full citation, abstract, references, citings, index terms

In very deep-submicron VLSI, certain manufacturing steps &mdash notably optical exposure, resist development and etch, chemical vapor deposition and chemical-mechanical polishing (CMP)&mdash have varying effects on device and interconnect features depending on local characteristics of the layout. To make these effects uniform and predictable, the layout itself must be made uniform with respect to certain density parameters. Traditionally, only foundries have performed the p ...

# 19 Image-based motion blur for stop motion animation

Gabriel J. Brostow, Irfan Essa

# August 2001 Proceedings of the 28th annual conference on Computer graphics and interactive techniques

Full text available: pdf(807.21 KB)

Additional Information: full citation, abstract, references, citings, index terms

Stop motion animation is a well-established technique where still pictures of static scenes are taken and then played at film speeds to show motion. A major limitation of this method appears when fast motions are desired; most motion appears to have sharp edges and there is no visible motion blur. Appearance of motion blur is a strong perceptual cue, which is automatically present in live-action films, and synthetically generated in animated sequences. In this paper, we present an approach fo ...

**Keywords**: animation, computer vision, image-based rendering, motion blur, stop motion animation, temporal antialiasing, video post-processing

20 Pen computing: a technology overview and a vision

André Meyer

July 1995 ACM SIGCHI Bulletin, Volume 27 Issue 3

Full text available: pdf(5.14 MB)

Additional Information: full citation, abstract, citings, index terms

This work gives an overview of a new technology that is attracting growing interest in public as well as in the computer industry itself. The visible difference from other technologies is in the use of a pen or pencil as the primary means of interaction between a user and a machine, picking up the familiar pen and paper interface metaphor. From this follows a set of consequences that will be analyzed and put into context with other emerging technologies and visions. Starting with a short historic ...

Results 1 - 20 of 41

Result page:  $1 \quad \underline{2} \quad \underline{3}$ next

The ACM Portal is published by the Association for Computing Machinery. Copyright © 2004 ACM, Inc. Terms of Usage Privacy Policy Code of Ethics Contact Us

Useful downloads: Adobe Acrobat Q QuickTime Windows Media Player